

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**  
( Not for submission under 37 CFR 1.99)

Application Number	10517575
Filing Date	2004-12-09
First Named Inventor	Victor Lu
Art Unit	2813
Examiner Name	Monica D. Hanneen
Attorney Docket Number	H0004019.68746 US - 4780

**U.S.PATENTS**

Examiner Initial*	Cite No	Patent Number	Kind Code <sup>1</sup>	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	3884702		1975-05-20	Unitika, Ltd.	
	2	4299938		1981-11-10	Ciba-Geigy Corporation	
	3	4349609		1982-09-14	Fujitsu Limited	
	4	4430153		1984-02-07	International Business Machines	
	5	4587138		1986-05-06	Intel Corporation	
	6	4863827		1989-09-05	American Hoechst Corporation	
	7	4910122		1999-03-20	Brewer Science, Inc.	
	8	4935583		1990-06-19	Kyle, James C.	

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9	4935320		1990-06-19	Ciba-Geigy Corporation	
10	4950583		1990-08-21	Brewer Science Inc.	
11	5100503		1992-03-31	NCR Corporation	
12	5126289		1992-06-30	AT&T Bell Laboratories	
13	5403680		1995-04-04	Osaka Gas Company, Ltd.	
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17	5674648	A	1997-10-07	Brewer et al.	
18	4191571		1980-03-04	Nonogaki et al.	

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**U.S.PATENT APPLICATION PUBLICATIONS**

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Examiner Initial*	Cite No	Publication Number	Kind Code <sup>1</sup>	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

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**FOREIGN PATENT DOCUMENTS**

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	1	Crivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 97-109.	<input type="checkbox"/>
	2	Degussa, "Silanes for Adhesives and Sealants," 18-19, available at <a href="http://www.dynasylan.com">www.dynasylan.com</a> .	<input type="checkbox"/>
	3	Lamola, A. et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>

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4	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," <i>Advances in Resist Technology and Processing</i> , Proc., SPIE vol. 469, 30-37 (1984). <input type="checkbox"/>
5	McKean et al., "Characterization of a Novolac-Based Three-Component Deep-UV Resist," <i>Chem. Mater.</i> (1990) 2, 619-624. <input type="checkbox"/>
6	Nalamasu et al., "Development of a Chemically Amplified Positive (CAMP) Resist Material for Single Layer Deep-UV Lithography," <i>Advances in Resist Technology and Processing VII</i> , SPIE 1262, 32-41 (1990). <input type="checkbox"/>
7	Silverstein et al., "Spectrometric Identification of Organic Compounds," 4th Ed. John Wiley & Sons 1991, 309-311. <input type="checkbox"/>
8	Willson, C.G., "Organic Resist Materials - Theory and Chemistry," <i>Introduction to Microlithography</i> , American Chemical Society, 87-159 (1983). <input type="checkbox"/>
9	Hawley's Condensed Chemical Dictionary, 11th ed., 85-86, <b>Van Nostrand Reinhold Company, New York (1987)</b> . <input type="checkbox"/>
10	"HD Micro Puts Out Positive Polyamide," <i>Electronic News</i> , June 19, 2000. <input type="checkbox"/>
11	Jaskot et al., <i>Toxicological Sciences</i> , 22(1): 103-112 (1994). <input type="checkbox"/>
12	<del>Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," <i>Advances in Resist Technology and Processing</i>, Proc., SPIE vol. 469, 30-37 (1984).</del> <input type="checkbox"/>
13	Yusuke Izumi et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," <i>Tetrahedron Letters</i> , Vol. 32, No. 36, pp 4744 (1991). <input type="checkbox"/>

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**EXAMINER SIGNATURE**

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